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乙二醇在电沉积中的应用

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摘要: 纯乙二醇(EG)和乙二醇-离子液体(EG-ILs)作为电解液在电沉积中进行了大量的应用。对EG体系中电沉积半导体材料、热电材料和金属单质进行总结,发现EG作为有机溶剂,具有较高的沸点而适合较大范围温度下的电沉积,电沉积温度从高温往室温发展,能通过添加剂和工艺参数对镀层进行调控。对EG-ILs体系中电沉积磁性材料、耐蚀材料和催化材料进行总结,发现在EG-ILs中电沉积得到镀层材料的耐腐蚀和催化性能优异。综述了金属在EG镀液中的电沉积机理。

关键词: 乙二醇;电沉积;有机溶剂;离子液体

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The application of ethylene glycol in electrodeposition

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Abstract: Ethylene glycol (EG) and ethylene glycol-ionic liquids (EG-ILs) have found extensive applications as electrolytes in electrodeposition. A comprehensive overview of semiconductor materials, thermoelectric materials, and elemental metals electrodeposited in the EG system reveals EG's effectiveness as an organic solvent due to its high boiling point, making it suitable for electrodeposition across a broad temperature range. The evolution of electrodeposition temperatures from high to ambient temperatures and the ability to finely control coating properties through additives and process parameters are notable aspects. In the EG-ILs system, a summary of electrodeposited magnetic materials, corrosion-resistant materials, and catalytic materials demonstrates that coatings obtained in EG-ILs exhibit outstanding corrosion resistance and catalytic performance. This review also delves into the electrodeposition mechanism of metals in EG plating solutions.

Keywords: ethylene glycol; electrodeposition; organic solvent; ionic liquids

电沉积体系可分水溶液、高温熔盐、离子液体和有机溶剂4类。水溶液体系^[1-3]中电沉积往往伴随着析氢反应,或者需要添加各种助剂,从而镀层中掺杂各种元素等,导致镀层质量变差;高温熔盐体系^[4-5]

中需要高温条件,能耗较大,且设备昂贵;离子液体^[6-7](ILs)因电化学窗口宽、导电率高和热稳定性好等优点而受到科研人员关注,在ILs中电沉积几乎无析氢反应发生,镀层平整致密,晶粒常可达到纳米

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级别,但ILs价格比较昂贵,离实际应用还有一段较长的路;有机溶剂容易挥发,对环境和人体有一定的危害。乙二醇(EG)其沸点较高,适用温度宽,不易产生蒸气被人吸入体内,且价格便宜而被用于电沉积各种材料^[8]。EG常和ILs混合使用,既能保持ILs的特性,且能降低成本,对水和空气保持长久的稳定性^[9]。

1 纯乙二醇在电沉积中的应用

纯EG应用于电沉积的研究已有三十多年的历史,能适用于较高温度下的电沉积,也能在室温下进行电沉积。目前报道纯EG最高电沉积的温度是175 °C。

1.1 电沉积半导体材料

1988-1989年间,Gore和Pandey^[10-11]在非水溶液EG中研究了电沉积条件对镀层结构和表面形貌的影响。结果表明:在EG体系中,低于130 °C下不利于CdTe镀层的形成,在高温(130 °C)可以沉积得到CdTe镀层,且随着镀液温度的升高,晶粒尺寸有增大趋势;恒电流沉积有利于得到富Cd的CdTe合金镀层;CdTe镀层生长较为均匀,晶粒接近球形且连接良好。1992年,Pandey等^[12]在EG镀液中电沉积CdTe镀层,并通过控制电流密度(<1.28 mA·cm⁻²)来得到富Te镀层,而较高电流密度下的电沉积会引起严重的裂纹,并有利于富Cd镀层的形成;在电流密度≤2 mA·cm⁻²的恒电流电沉积或在-0.55 V(vs. SCE)的恒电位电沉积得到无裂纹CdTe镀层。1993年,Pandey等^[13]在160 °C下,通过在EG体系中添加KI,不仅提高了在Ni电极上的镀层附着力,而且阻碍了离子络合。1994年,Pandey等^[14]在EG镀液中恒电位电沉积CdTe镀层,并研究了其形态、结构和组成的演化,明确了制备具有均匀颗粒形态的化学计量CdTe镀层的实验条件。随着研究的进展,在EG中电沉积向低温方向发展。1997年,Lade和Lokhande^[15]利用EG在90 °C下电沉积CdS镀层,XRD结果表明:CdS镀层为多晶态,具有单六方相。2000年,Lade等^[16]利用EG镀液在不同的基材上,在80 °C的沉积温度下,采用恒电流电沉积法,制备了表面致密、均匀、无裂纹的CdTe镀层。2007-2008年间,Pawar等^[17]在EG镀液中通过恒电位电沉积法,在不锈钢和氟掺杂氧化锡(FTO)玻璃基底上得到了CdSe镀层,利用光电化学技术优化了沉积电位、镀

液成分、镀液温度、镀液pH值和沉积时间等制备参数。扫描电镜(SEM)研究表明,晶粒均匀分布在整个基体表面;X射线衍射(XRD)研究表明,所制备的CdSe镀层具有近似化学计量的六方多晶结构。Pawar等^[18]在室温下利用光电化学(PEC)表征技术优化了EG镀液中电沉积CdSe镀层Fe的掺杂浓度,用循环伏安法(CV)研究了沉积机理和Fe的掺入。研究表明掺杂Fe的CdSe镀层比未掺杂Fe的CdSe薄膜具有更高的光敏性,且掺杂后其镀层表面形貌完全改变。

1.2 电沉积热电材料

2012年,Nguyen等^[19]从EG中电沉积BiTe热电薄膜,Bi和Te均由Bi³⁺和Te⁴⁺一步还原,还原电位分别大于+0.2 V和+0.55 V相对于标准氢电极(vs. SHE)。从旋转圆盘电极实验中研究了电沉积反应的动力学,通过Koutecky-Levich方程得到Bi和Te的扩散系数(d_0)和还原速率常数相近,且也与水溶液中的 d_0 和还原速率常数接近。从含有1 mol/L Bi(NO₃)₃和TeCl₄的溶液中,在电流密度高达500 mA·cm⁻²(~102 μm·h⁻¹)的条件下,获得了化学计量的Bi₂Te₃薄膜,其组成分布均匀。通过塞贝克系数的测量,可以得到p型和n型BiTe热电材料薄膜。同年,Yamamoto等^[20]研究了在EG中电沉积CoSb热电半导体薄膜。通过控制镀液成分EG-CoCl₂-Sb-Cl₃(各组分浓度为90.0 mol%-9.3 mol%-0.7 mol%)和阴极电流密度(5~30 mA·cm⁻²),得到在给定的温差下表现出p型热电转换含23.6 mol%~76.4 mol% CoSb₃的CoSb合金薄膜。2014年,Wu等^[21]从无氯的EG镀液中利用旋转圆盘电极在单个电镀槽中通过脉冲电位电沉积得到n型热电Bi₂Te₃/(Bi_{1-x}Sb_x)₂Te₃(x<0.4)多层膜。通过改变沉积时间,可以控制沉积层的厚度,降低转速或在较高过电位下,电沉积能提高(Bi_{1-x}Sb_x)₂Te₃三元合金中的Te含量。

1.3 电沉积金属单质

1993年,Singh和Sadeghi Sarabi^[22]在EG镀液中成功制备了光亮和均匀的金属Ni镀层。2015年,Neuróhr等^[23]在EG镀液中制备了层片状的金属Ni镀层。2014年,Maltanava等^[24]制备了一种稳定的含SnCl₄·5H₂O和硼酸的非水电解质EG或PG,用于电化学镀锡。EG或PG镀液的镀Sn速率为14 μm·h⁻¹,电流产率为91%~93%。由于阴极上没有Sn晶须的形成和氢气的析出,沉积速率和电流效率明显高于

水溶液。2018~2019年,Panzeri等^[25-27]从EG镀液中成功的制备了金属Fe、Zn和Co镀层。在Fe²⁺和Fe³⁺的EG镀液电沉积Fe,发现Fe³⁺不能一步还原成Fe;恒电位电沉积最好的结果是在Fe²⁺(-1.7 V vs. Pt)和Fe³⁺(-2.3 V vs. Pt),其Fe镀层不含氧;XRD显示沉积纳米晶是体心立方(BCC),沿(110)晶面择优取向;振动样品磁强计(VSM)分析表明,饱和磁化率良好^[25]。以EG和乙酸盐为前体盐,在无氯化物的有机溶液中进行了Zn的电沉积。其阴极电流效率为85%;SEM和XRD分析表明,镀层致密,晶粒大,呈沿(002)或(102)方向优先取向的六边形微观结构^[26]。Co²⁺在EG镀液的还原过程是不可逆的,法拉第效率高(85%~90%),Co的d₀为2.29×10⁻⁶ cm²·s⁻¹;Co镀层XRD分析表明,镀层是密排六方结构(HCP),沿(100)方向具有择优取向;VSM强调了Co薄膜在平面内磁化的事^[27]。

2 乙二醇-离子液体在电沉积中的应用

EG常和ILs混合使用,它既能保持ILs的特性,又能降低成本,且对水和空气能保持长久的稳定性。

2.1 电沉积磁性材料

2008年,Yang等^[28]利用多孔阳极氧化铝模板法在1-乙基-3-甲基咪唑氯离子液体和EG混合物中制备Co纳米线,其具有很强的垂直磁各向异性,可以作为垂直磁记录薄膜。2013年,Zhao等^[29]在氯化胆碱(ChCl)-EG(DES)电沉积得到Fe-Ga合金,并通过添加草酸得到含17 at.% Ga的Fe-Ga合金,其磁滞循环饱和磁化强度约为1.7 T。2017年,Pereirazai等^[30]在ChCl-EG和ChCl-尿素(U)中电沉积得到Co-Sn合金,用ChCl-EG制备的Co-Sn合金比用ChCl-U制备的Co-Sn合金具有更高的矫顽力场。

2.2 电沉积耐蚀材料

2011年,Gu等^[31]在DES中电沉积Ni镀层,纳米晶Ni镀层具有较强的负腐蚀电位,为黄铜基板提供了牺牲阳极保护。同年,Gu和Tu^[32]利用ChCl基ILs在90 °C高温下程序化电化学沉积制备纳米结构Ni镀层,电沉积Ni镀层不需要任何低表面能材料的进一步修饰就能获得超疏水表面,且超疏水Ni镀层在电化学测试中表现出明显的钝化现象,增强了基体在水溶液中的耐蚀性。2012年,You等^[33]在DES中电沉积Ni和3种不同Co含量的Co-Ni合金,随着Co含量的增加,其耐蚀性能下降。Saravanan和

Mohan^[34]在DES中采用直流电沉积技术(DCD)和脉冲电沉积技术(PED)研究了Cu和低碳钢基体上Co-Cr合金的电沉积,极化曲线和电化学阻抗谱结果表明,与Co_{80.04}Cr_{19.95}(DCD)和裸软钢基体相比,PED沉积Co_{65.44}Cr_{34.55}合金具有较高的交流阻抗电荷传递电阻(Rct)和较低的腐蚀电流密度(Icorr)。2015年,Fashut等^[35]采用乙二胺四乙酸(EDTA)和氯化铵(NH₄Cl)两种添加剂从DES中电沉积Zn-Ni合金镀层。其中添加NH₄Cl得到的Zn-Ni合金镀层的耐腐蚀性优于添加EDTA得到的Zn-Ni合金镀层耐腐蚀性。Zhang等^[36]在DES中电沉积Cr和Cr-P镀层。发现Cr³⁺的还原过程分为两步,加入NH₄H₂PO₂可促进Cr³⁺的控制步骤;且Cr³⁺在DES中电沉积非常敏感,电位(电流)控制在-1.2~-1.3 V(vs. Ag)(7~10 mA·cm⁻²)。电刷镀Ni层是在Fe基体上获得光滑致密的Cr或Cr-P镀层的必要条件;虽然镀层无裂纹,但是镀层中仍存在内部应力和Cl⁻,导致在腐蚀介质中存在裂纹和点蚀。对镀层的结构和成分进行了深入分析,Cr和Cr-P镀层在3.5 wt.% NaCl溶液和0.1 M H₂SO₄溶液中的腐蚀行为有较大差异。2019年,Li等^[37]在DES中电沉积Co-Ni合金,在-0.9 V (vs. SCE)~-1.1 V (vs. SCE)的电位下电沉积,得到Co含量在2.94wt.%~11.56 wt.%的范围内,Co含量的增加,有利于耐蚀性能的增强。其中-1.0 V (vs. SCE)所得到合金镀层的耐蚀性最好。Winiarski等^[38]在DES中电沉积纳米晶Ni镀层,并在0.05 mol/L NaCl溶液中测试纳米晶Ni镀层的耐蚀性能。

2.3 电沉积催化材料

2013年,Vijayakumar等^[39]在DES中电沉积Ni-Co-Sn三元合金,并比较了其与Ni-Sn和Co-Sn二元合金的析氢催化性能。其中Ni-Co-Sn三元合金在1 mol/L KOH溶液中的交换电流密度(j₀)最高,因此可以用作析氢反应应用的潜在候选材料。2016年,Gao等^[40]在DES中利用恒电位电沉积得到多孔Ni-Cu合金,其最优工艺条件下制备的多孔Ni-Cu合金在1 mol/L KOH溶液中的析氢过电位η₁₀=128 mV,j₀=0.151 mA·cm⁻²。多孔Ni-Cu合金有高的析氢催化性归因于Ni和Cu的协同作用及独特的三维与粗糙的垂直暴露纳米片多孔结构。2017年,Gao等^[41]从DES报道了一个简单一步电沉积路线且多孔镍钼合金微球(钼镍MS)薄膜直接电镀在铜薄片,作为

一种在1 mol/L KOH溶液中高效、耐用的析氢和析氧的催化剂。制备的Ni-Mo MS/Cu作为析氢阴极,其Tafel斜率(b)为49 mV·dec⁻¹,析氢过电位 $\eta_{20}=63$ mV,具有较好的催化析氢的性能;作为析氧阳极,该催化剂还具有良好的析氧催化活性, $b=108$ mV·dec⁻¹,在析氧过电位 $\eta_{20}=335$ mV;该双功能催化剂作为对称双电极电解水系统的阴极和阳极,达到10 mA·cm⁻²的整体水分裂电流密度仅需要1.59 V的电池电压。Zeng等^[42]通过DES一步电沉积的方法成功地制备了直接生长在铜线(CW)上的三维叠层掺杂S的花椰菜状Ni微球(NiS_x/CW),作为析氢的高活性电催化剂。结果表明,S的引入导致了花椰菜状结构的形成,其催化活性显著增强;此外,Ni网络与掺杂的S原子之间的强电子相互作用也是催化活性高的原因之一。2018年,Sun等^[43]在DES中,采用一步电沉积的方法,在铜箔上制备了自支撑的P掺杂镍超结构薄膜(NiP_x),用于析氢催化。NiP_x薄膜的高效催化活性源于P掺杂导致的活性位点的富集和电子导电性的增强,这也改变了材料的表面电子结构,使水的离解能垒较低,H的吸附自由能较好。2019年,Kopczyński和Lota^[44]用DES电沉积Ce-Ni镀层作为析氢电极。同年,He等^[45-46]在1-乙基-3-甲基咪唑硫酸氢盐([EMIM]HSO₄)-EG体系中电沉积Co及Co-Ni合金镀层用于析氢电催化。Protsenko等^[47]应用DES制备纳米晶Ni和Ni/TiO₂镀层作为析氢反应的电催化剂。Shaban等^[48]在DES循环伏安电沉积Sn-Ag合金用于析氢。Vo等^[49]提出了一个在DES中制备自支撑的Ni-Fe合金镀层直接生长在铜箔上。与水溶液电沉积不同的是,由于沉积窗口的增大和二次反应的抑制,在DES中沉积的合金成分与其镀液中沉积的合金成分相同。通过在DES中合理优化镀Ni-Fe比例,Ni-75%Fe镀层的析氧性能最好, $\eta_{10}=316$ mV, $b=62$ mV·dec⁻¹。2020年,Wang等^[50]将镍活性炭(AC)粒子加入以Pt为对电极、Ag为参比电极的DES电解槽中,得到了花椰菜状的三维NiACAgPt复合材料。在碱性介质中 $\eta_{10}=48$ mV, $b=35$ mV·dec⁻¹,该催化剂表现出良好的催化性能。同年,Sun等^[51]用DES电沉积高电化学活性的Ti/SnO₂-Sb电极。这种新型Ti/SnO₂-Sb-DES电极对亚甲基蓝的脱色速率常数为0.571 h⁻¹,加速使用寿命为12.9 h(100 mA·cm⁻²;0.5 mol/L H₂SO₄)。

3 金属在乙二醇镀液中的电沉积机理

到目前为止,人们主要研究了Co^[8,27,45],Ni^[52],Zn^[26,53]和Fe^[25]在EG镀液中的电沉积机理,其它单金属和合金在EG镀液的电沉积机理的研究还较少。

3.1 金属在乙二醇镀液中电化学行为

Panzeri等^[27]和He等^[8]通过CV研究了Co在EG中电化学行为,结果表明:Co(II)的还原是一步不可逆的还原反应,得到的Co镀层晶粒平均尺寸是19 nm。He等^[8]在EG中添加[EMIM]HSO₄,Co的电化学行为并未发生变化,同样的有一个典型的电流交叉环,这说明Co(II)的还原过程是通过过电位驱动的成核和生长过程,也是一个受扩散控制的过程。特别是在EG中添加[EMIM]HSO₄后,Co(II)的成核过电位可以更负,如图1所示,预示着Co镀层晶粒更细,得到的Co镀层晶粒平均尺寸是11 nm^[45]。Gong等^[52]采用CV研究了Ni在14.3%~85.7%(摩尔分数)的甜菜碱盐酸盐-EG中的电化学行为。结果表明,Ni²⁺在玻碳电极(GC)上还原为Ni是一个扩散控制的准可逆过程。Panzeri等^[26]利用核磁共振氢谱(¹H-NMR)在EG和醋酸锌镀液中发现EG和锌的络合物;采用CV得到Zn²⁺在Pt电极上还原为Zn是一个受动力学控制的过程。马军德等^[53]将EG添加到ZnCl₂-1-甲基-3-乙基咪唑(EMIC)离子液体中,采用CV研究EG-EMIC中Zn电沉积的阴极过程。结果表明,随着EG含量的增加到60%,Zn的初始析出电位能正移到0 V。

3.2 金属在乙二醇镀液中电结晶机理

He等通过计时电流法(CA)研究了在EG体系中不同温度下Co的成核方式。结果表明,在低温下,Co的成核方式更符合三维连续成核,随着温度升高,Co的成核方式更符合三维瞬时成核^[8]。在EG-[EMIM]HSO₄体系中,Co的成核方式受电位影响,是扩散控制生长过程中低过电位下的三维渐进成核和高过电位下的瞬时成核^[45]。马军德等^[53]将EG添加到ZnCl₂-EMIC离子液体中,采用CA研究了Zn的成核机理,研究表明EG对Zn的形核方式没有影响,电结晶过程都是三维瞬时成核半球形扩散长大过程。

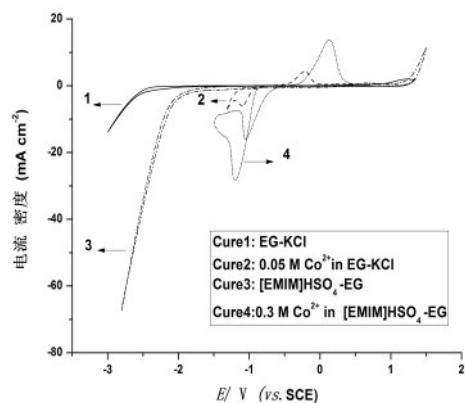


图1 温度 323 K, 扫描速度 50 mV s^{-1} 的循环伏安曲线^[8, 45]
Fig. 1 Cyclic voltammograms at 323 K with scan rate of 50 mV s^{-1} ^[8, 45],

4 结语与展望

近些年来,关于EG体系电沉积的研究有了很大的进展,在EG体系中电沉积可制备多种材料,在EG中添加离子液体等电沉积可制备各种功能性材料。但在EG体系中电沉积机理的理论研究还很少涉及,为了使EG镀液电沉积应用范围更加广泛,对EG体系中电沉积金属及合金的理论分析还需要深入研究。

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